

IN THE CLAIMS:

Kindly cancel claims 2, 3, 8, 9 and 21, and amend the remainder of the claims, as follows:

1. (Once Amended) A polishing tool for polishing silicon wafers, said tool comprising an endless belt which includes a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane, wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction and said polishing layer includes two layers which are of different hardness.

2. (Canceled)

3. (Canceled)

4. (Previously Presented) A polishing tool according to claim 1 wherein an exposed surface of said polishing layer is formed with grooves.

5. (Once Amended) A polishing tool according to claim 3 1 wherein an upper of said two layers includes beads of plastic, glass or a soluble material.

6. (Previously Presented) A polishing tool according to claim 1 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.

7. (Once Amended) An endless belt for polishing semiconductor wafers comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane, wherein said fabric is woven and includes aramid yarns oriented in the lengthwise

direction, and said polishing layer comprises two layer which are of different hardness.

8. (Canceled)

9. (Canceled)

10. (Previously Presented) An endless belt according to claim 7 wherein an exposed surface of said polishing layer is formed with grooves.

11. (Once Amended) An endless belt according to claim 9₇ wherein an upper of said two layers includes beads of plastic, glass or a soluble material.

12. (Previously Presented) An endless belt according to claim 7 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.

13. (Once Amended) An endless belt for polishing optical flats comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane, wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction and said polishing layer includes two layers which are of different harness.

14. (Canceled)

15. (Canceled)

16. (Previously Presented) An endless belt according to claim 13 wherein an exposed surface of said polishing layer is formed with grooves.

17. (Once Amended) An endless belt according to claim 15₃ wherein an upper of said two layers includes beads of plastic, glass or a soluble material.

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18. (Previously Presented) An endless belt according to claim 13 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.

19. (Once Amended) An endless belt for polishing mirrors comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane, said polishing layer including two layers which are of different hardness.

20. (Previously Presented) An endless belt according to claim ~~20~~¹⁹ wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction.

21. (Canceled)

22. (Previously Presented) An endless belt according to claim 19 wherein an exposed surface of said polishing layer is formed with grooves.

23. (Once Amended) An endless belt according to claim ~~21~~¹⁹ wherein an upper of said two layers includes beads of plastic, glass or a soluble material.

24. (Previously Presented) An endless belt according to Claim 19 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.

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